Fractional bond model for silicon clusters

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(Received 20 July 1998; revised manuscript received 8 September 1998)

 Si_6 and Si_7 are the two largest clusters with confirmed geometries experimentally. The apex atoms in the pentagonal bipyramidal structure for Si_7 have a coordination number of 6, completely different from the tetrahedral structure of the diamond lattice, and never given a definite explanation so far. In this paper, we suggest that atomic bondings in small silicon clusters be the unsaturated covalent, rather than covalent-bond. We introduce the number of bond order and defined it as the ratio of the number of valence electron of an atom to the effective coordination number of the *i*th atom, which can be smaller than 1 or greater. An *ad hoc* tight-binding model (fractional bond model) for silicon clusters is constructed by explicitly incorporating the dependence of hopping integrals between two atoms on the number of bond order, and their ground state structures of silicon clusters are performed. The results indicate that this model is successful in determining the structures of free small silicon clusters. [S0163-1829(99)00839-5]

An enormous effort has been devoted to determining the structures of free silicon clusters,¹⁻¹⁷ but one has not paid sufficient attention to the problem why some atoms in silicon clusters have a coordination number greater than 4. For example, the ground-state structure of Si₇ is a pentagonal bipyramid with D_{5h} symmetry experimentally confirmed.¹⁸ The apex atoms in the pentagonal bipyramidal structure have a coordination number of 6, completely different from the tetrahedral structure of the diamond lattice. It virtually reflects the micromechanism of atomic bonding in silicon clusters. Therefore, it is necessary to give a concise but clear physical picture for understanding such system.

Theoretical methods used to describe the structural properties of silicon clusters can be classified into the three groups: (i) Ab initio quantum-chemical techniques (Hartree-Fock + electron correlation)^{19–23} and density-functional methods.²⁴⁻²⁶ However, they are time consuming. (ii) Various types of interatomic potentials beyond pair potentials,27-30 where the many-body terms or the dependence on the local environment are incorporated. This type of method cannot deal directly with the change in electronic structure. (iii) Semiempirical tight-binding schemes, 31-34 such as nonorthogonal tight-binding (NTB) moleculardynamics technique, and improved versions.^{31,32} This group is acceptable for the larger number of tractable atoms and the consumption of computing power. It can give the information of electronic structure as well. Here, we propose the fractional bond model proposed, which is completely different from the known tight-binding schemes. The hopping integrals between two atoms are assumed to depend on four factors: number of bonding electrons, number of bonds, bonding strength of per atom, and interatomic distance, in which the number of bonding electron has something to do with the number of bond order.

On the basis of Pauling's suggestion for understanding bulk-metal systems,³⁵ we define the number of bond order as

$$n_{\rm bo} = \frac{n_{\rm ve}}{Z_i},\tag{1}$$

where n_{ve} and Z_i denote the number of valence electrons of an atom and the effective coordination number of the *i*th atom, respectively. The bonding strength per atom is defined as

$$b_s = \left(\frac{f}{N}\right)^{\delta},\tag{2}$$

where *N* is the atomic number of a cluster, δ an adjustable parameter, and *f* the bonding power. According to the theory of orbital hybridization, for the *spd* hybrids, the bonding power *f* can be written as

$$f = \sqrt{\alpha} + \sqrt{3\beta} + \sqrt{5\gamma},\tag{3}$$

where α , β , and γ are the components of orbitals *s*, *p*, and *d*, respectively. For example, $\alpha = \frac{1}{4}$, $\beta = \frac{3}{4}$, $\gamma = 0$, and f = 2 for the sp^3 hybrids.

The cohesive energy of the cluster $E_{\rm coh}$ can be written as a sum of the band-structure energy $E_{\rm bs}$ and the repulsive energy $E_{\rm rep}$ (Refs. 2 and 36)

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TABLE I. Parameters used in the present scheme for silicon clusters.

Hopping integrals							
$ss\sigma$	$sp\sigma$	$pp\sigma$	$pp\pi$				
4	3	2	2				
1.20	1.40	0.85	0.60				
-1.15	1.05	0.90	-0.50				
$\epsilon_p(\text{eV}) = -6.52^{\text{b}}$ $\alpha(\text{\AA}^{-1}) = 1.6$	$d_0(\text{\AA}) = 2.36^{\text{b}}$ $\chi_0(\text{eV}) = 0.19$	$\lambda_1(\text{\AA}^{-2}) = 1.086^{a}$	$\lambda_2(\text{\AA}^{-1}) = 8.511^{a}$				
	$\frac{ss\sigma}{4}$ -1.15 $\epsilon_p(eV) = -6.52^{b}$ $\alpha(Å^{-1}) = 1.6$	Hopping integrals ss σ sp σ 4 3 1.20 1.40 -1.15 1.05 $\epsilon_p(eV) = -6.52^{b}$ $d_0(Å) = 2.36^{b}$ $\alpha(Å^{-1}) = 1.6$ $\chi_0(eV) = 0.19$	Hopping integrals ss σ sp σ pp σ 4 3 2 1.20 1.40 0.85 -1.15 1.05 0.90 $\epsilon_p(eV) = -6.52^{b}$ $d_0(\text{\AA}) = 2.36^{b}$ $\lambda_1(\text{\AA}^{-2}) = 1.086^{a}$ $\alpha(\text{\AA}^{-1}) = 1.6$ $\chi_0(eV) = 0.19$ $\lambda_1(\text{\AA}^{-2}) = 1.086^{a}$				

^aReference 34.

^bReference 31.

$$E_{\rm coh} = E_{\rm bs} + E_{\rm rep} \,. \tag{4}$$

The band-structure energy is given by

$$E_{\rm bs} = \sum_{\alpha} n_{\alpha} \epsilon_{\alpha} - N \sum_{\alpha} n_{\alpha}^{0} \epsilon_{\alpha}^{0}, \qquad (5)$$

where ϵ_{α}^{0} are the atomic levels. The n_{α} and n_{α}^{0} are the occupancy of the orbital α of the cluster and of the isolated atoms, respectively. The electronic levels ϵ_{α} of the cluster can be obtained from a tight-binding Hamiltonian of the form

$$H_{\rm tb} = \sum_{i,\alpha} \epsilon^0_{\alpha} a^{\dagger}_{i\alpha} a_{i\alpha} + \sum_{i,\alpha} \sum_{j,\beta} t_{i\alpha,j\beta} (a^{\dagger}_{i\alpha} a_{j\beta} + {\rm H.c.}), \quad (6)$$

where $t_{i\alpha,j\beta}$ denote electronic hopping integrals between different sites *i* and *j*. They are assumed to have the following form:

$$t_{i\alpha,j\beta} = C_{\alpha\beta} n_{be}^{\mu} r_{ij}^{-\nu} b_s Z_i, \qquad (7)$$

where n_{be} is the number of bonding electrons and is read as

$$n_{\rm be} = 2 \times n_{\rm bo} = 2 \times \frac{4}{Z_i}.$$
(8)

Here, numbers 2 and 4 represent the electronic number per bond and the number of valence electrons of an atom, respectively. r_{ij} is a distance between the *i*th and *j*th atoms and the exponent ν is dependent on the orbitals α and β . Z_i is the effective coordination number of the *i*th atom and is written as³⁴

$$Z_{i} = \sum_{j \neq i} \exp[-\lambda_{1}(r_{ij} - R_{i})^{2}], \qquad (9)$$

where R_i is the minimum interatomic distance of the neighbors of *i*th atom and is given by

$$R_{i} = \sum_{j \neq i} r_{ij} e^{-\lambda_{2} r_{ij}} \left[\sum_{j \neq i} e^{-\lambda_{2} r_{ij}} \right]^{-1}.$$
 (10)

The repulsive energy $E_{\rm rep}$ is assumed to have the form³¹

$$E_{\text{rep}} = \sum_{i} \sum_{j>i} \chi(r_{ij}), \qquad (11)$$

and $\chi(r)$ is taken to be short-ranged for scaling exponentially with distance $\chi(r) = \chi_0 e^{-4\alpha(r-d_0)},$ (12)

where the parameter d_0 is taken from Ref. 31, α and χ_0 are adjustable parameters. The values of the parameters are listed in Table I.

In order to test present model, an unbiased global search for the ground-state structures of small silicon clusters has been carried out by means of genetic algorithms (GA's),^{37,38} an optimization strategy based on modeling of biological evolution. The results of the cohesive energies of the groundstate structures for the Si_N from N=2 to N=10, together with the calculated second finite difference of the total minimum energy, $\Delta_2 E(N) = E(N+1) + E(N-1) - 2E(N)$, are summarized in Table II, and compared with the previous *ab initio* values^{20,21} and the NTB calculations.³¹ The optimized geometries of Si_N (N=6-10) clusters are displayed in Fig. 1.

The minimum energy structure for Si₃ is found to be an isosceles triangle with C_{2v} symmetry, in agreement with *ab initio* results.²⁰ For Si₄, the stable structure in our case is a distorted tetrahedron rather than a planar rhombus. In the case of Si₅, the lowest energy configuration is found to be a face-capped tetrahedron with C_{2v} symmetry, not in agreement with the *ab initio* results. This structure is the lowest triplet for Si₅ lying on only 0.607 eV higher in energy than the ground-state singlet (compressed trigonal bipyramid) at the MP4/6-31G* level.²¹ For the Si₆ cluster, we have shown two energy structures in Fig. 1: an octahedron with D_{4h}

TABLE II. Cohesive energies $\langle E \rangle$ (eV/atom) and second finite difference $\Delta_2 E$ (eV) for Si_N clusters from N=2 to N=10, and compared with the previous *ab initio* values and the NTB calculations.

N	$\begin{array}{c} Ab \ initio \ ^{\rm a} \\ \langle E \rangle \end{array}$	$\Delta_2 E$	NTB ^b $\langle E \rangle$	$\Delta_2 E$	Present work $\langle E \rangle$	$\Delta_2 E$
2	1.56		1.55		1.568	
3	2.54	-0.56	2.48	-0.74	2.363	-0.89
4	3.17	1.24	3.13	0.80	2.982	0.32
5	3.3	-1.28	3.36	-0.70	3.289	-0.53
6	3.6	0.10	3.63	0.09	3.582	0.13
7	3.8	2.40	3.81	1.32	3.773	0.81
8	3.65	-0.60	3.78	-1.29	3.815	-1.53
9	3.6	-2.60	3.90	0.06	4.018	0.95
10	3.82		3.99		4.085	

^aReference 21. ^bReference 31.



FIG. 1. Geometries of the lowest energy structures of small silicon clusters from N=6 to 10 obtained using the fractional bond model.

symmetry has an average energy lower compared with the undistorted octahedron, which means that the distorted one is more stable due to Jahn-Teller effects. The lowest energy structure for Si₇ is the pentagonal bipyramid with D_{5h} symmetry, containing silicon atoms with coordination number greater than four. These are in excellent agreement with experimental observations.^{5,18}

For Si₈, the lowest energy structure is a distorted bicapped octahedron, and this octahedron is capped on adjacent faces. *Ab initio* calculation indicates that the most favorable arrangement corresponds to capping two opposite faces. It is likely that electron correlation effects are not fully included at the Hartree-Fock level. For Si₉, the C_{2v} distorted tricapped trigonal prism is its minimum energy structure, in agreement with the result suggested by Ordejón and collaborators.³² Meantime, they have pointed out that this

structure is also a minimum at the Hartree-Fock level as well as that in approximate density-functional theory. For Si₁₀, we find that the lowest energy structure is a distorted tetracapped trigonal prism, which is a Jahn-Teller distortion of the structure considered in Ref. 21. In fact, the lowest energy structures of Si₉ and Si₁₀ clusters can be derived from a pentagonal bipyramid with D_{5h} symmetry. The Si₇ cluster, therefore, can be visualized as the building block of Si₉ and Si₁₀ clusters.

Recently, Vasiliev et al.¹⁷ have carried out ab initio calculations for the polarizabilities of small semiconductor clusters, and confirmed the "metalliclike" nature of small semiconductor clusters, i.e., these species tend to have higher coordination number than that in the crystalline state. In addition, their work has still shown that Si₇ is the most stable one among Si_N (N=3-10) clusters since there is a minimum at N=7 in the plot of the average polarizabilities versus cluster size. From the calculated second finite difference of total energy $\Delta_2 E$ (see Table II) we have also shown that Si_N clusters with N=4, 7, and 9 are particularly stable, which are in good agreement with ab initio results²¹ and NTB calculations³¹ except for N=9. It may be deduced that there is a competition between the distorted tricapped trigonal prism and the distorted tricapped octahedron for Si₉. The former prevails due to containing a building block with size N=7. For Si₁₀, similar competition may exist, too. Very recently, Ho *et al.*³⁸ have found that in $12 \le N \le 18$ size range, the cluster geometries can be built on a structural motif consisting of a stack of Si₉ tricapped trigonal prisms. This also indicates that Si₉ tricapped trigonal prism is stable. Therefore, the maximum of the $\Delta_2 E$ for Si₉ is reasonable. Moreover, the geometries obtained for the other small silicon clusters by this model also appear "metalliclike" with the coordination number of some atoms more than 4. This kind of "metalliclike" nature for small silicon clusters comes from the unsaturated covalent bond. It must be pointed out that our model fails to give a planar rhombus for the lowest energy structure of Si₄, which has been proved by the experiments.^{5,18} A possible reason is that quantum effect may be so significant to dominate the lowest energy structure of Si₄. However, a quantum effect cannot be considered sufficiently in the tight-binding approximation.

In summary, we have presented the fractional bond model together with a genetic algorithm, to perform the lowest energy structures of Si_N clusters up to N = 10. Our results indicate that the distorted octahedron of Si_6 and pentagonal bipyramid of Si_7 , are in excellent agreement with those verified experimentally. The geometried structures given by this model imply that small silicon clusters are of the "metalliclike" nature, i.e., these species give preference to compact structures. This behavior is ascribed to the unsaturated covalent bond in such systems. In addition, the stability of Si_9 with distorted tricapped trigonal prism indicates that it can be viewed as a building block of clusters with larger size.

This work was financially supported by the National Natural Science Foundation of China.

- ¹T. P. Martin and H. Schaber, Z. Phys. B **35**, 61 (1979).
- ²D. Tománek and M. A. Schluter, Phys. Rev. Lett. **56**, 1055 (1986); Phys. Rev. B **36**, 1208 (1987).
- ³T. Slee, L. Zhenyang, and D. M. P. Mingos, Inorg. Chem. **28**, 2256 (1989).
- ⁴E. Kaxiras and K. A. Jackson, Phys. Rev. Lett. **71**, 727 (1993); Z. Phys. D **26**, 346 (1993).
- ⁵S. Li, R. J. Van Zee, W. Weltner, Jr., and K. Raghavachari, Chem. Phys. Lett. **243**, 275 (1995).
- ⁶J. R. Chelikowsky, K. M. Glassford, and J. C. Phillips, Phys. Rev. B 44, 1538 (1991).
- ⁷A. D. Mistriotis, G. E. Froudakis, P. Vendras, and N. Flytzanis, Phys. Rev. B 47, 10 648 (1993).
- ⁸M. V. Ramakrishna and A. Bahel, J. Chem. Phys. **104**, 9833 (1996).
- ⁹J. C. Grossman and L. Mitas, Phys. Rev. Lett. **74**, 1323 (1995); Phys. Rev. B **52**, 16 735 (1995).
- ¹⁰L. A. Curtiss, P. W. Deutsch, and K. Raghavachari, J. Chem. Phys. **96**, 6868 (1992).
- ¹¹U. Röthlisberger, W. Andreoni, and M. Parrinello, Phys. Rev. Lett. **72**, 665 (1994).
- ¹²A. Bahel and M. V. Ramakrishna, Phys. Rev. B **51**, 13 849 (1995).
- ¹³N. Binggeli and J. R. Chelikowsky, Phys. Rev. B **50**, 11 764 (1994).
- ¹⁴X. Jing, N. Troullier, D. Dean, N. Binggeli, J. R. Chelikowsky, K. Wu, and Y. Saad, Phys. Rev. B 50, 12 234 (1994).
- ¹⁵J. Pan and M. V. Ramakrishna, Phys. Rev. B **50**, 15 431 (1994).
- ¹⁶C. H. Patterson and R. P. Messmer, Phys. Rev. B **42**, 7530 (1990); R. P. Messmer and C. H. Patterson, Chem. Phys. Lett. **192**, 277 (1992).
- ¹⁷I. Vasiliev, S. Ögüt and J. R. Chelikowsky, Phys. Rev. Lett. **78**, 4805 (1997).
- ¹⁸E. C. Honea, A. Ogura, C. A. Murray, K. Raghavachari, W. O. Sprenger, M. F. Jarrold, and W. L. Brown, Nature (London) **366**, 42 (1993).
- ¹⁹K. Raghavachari and V. Logovinsky, Phys. Rev. Lett. **55**, 2853 (1985); K. Raghavachari, J. Chem. Phys. **83**, 3520 (1985).
- ²⁰K. Raghavachari, J. Chem. Phys. 84, 5672 (1986).

- ²¹K. Raghavachari and C. M. Rohlfing, J. Chem. Phys. **89**, 2219 (1988).
- ²²C. M. Rohlfing and K. Raghavachari, Chem. Phys. Lett. **167**, 559 (1990); J. Chem. Phys. **96**, 2114 (1992).
- ²³K. Raghavachari and C. M. Rohlfing, Chem. Phys. Lett. 143, 428 (1988); 198, 521 (1992); J. Chem. Phys. 94, 3670 (1991).
- ²⁴P. Ballone, W. Andreoni, R. Car, and M. Parrinello, Phys. Rev. Lett. **60**, 271 (1988).
- ²⁵U. Röthlisberger, W. Andreoni, and P. Giannozzi, J. Chem. Phys. 96, 1248 (1992).
- ²⁶Th. Frauenheim, F. Weich, Th. Köhler, S. Uhlmann, D. Porezag, and G. Seifert, Phys. Rev. B **52**, 11 492 (1995).
- ²⁷ J. Tersoff, Phys. Rev. Lett. **56**, 632 (1986); Phys. Rev. B **37**, 6991 (1988).
- ²⁸B. C. Bolding and H. C. Andersen, Phys. Rev. B **41**, 10 568 (1990).
- ²⁹H. Balamane, T. Halicioglu, and W. A. Tiller, Phys. Rev. B 46, 2250 (1992).
- ³⁰X. G. Gong, Q. Q. Zheng, and Y. Z. He, J. Phys.: Condens. Matter 7, 577 (1995).
- ³¹M. Menon and K. R. Subbaswamy, Phys. Rev. Lett. 67, 3487 (1991); Phys. Rev. B 47, 12 754 (1993); 50, 11 577 (1994); 51, 17 952 (1995); 55, 9231 (1996).
- ³²P. Ordejón, D. Lebedenko, and M. Menon, Phys. Rev. B **50**, 5645 (1994).
- ³³I. Kwon, R. Biswas, C. Z. Wang, K. M. Ho, and C. M. Soukoulis, Phys. Rev. B **49**, 7242 (1994).
- ³⁴S. Sawada, Vacuum **41**, 612 (1990); M. Kohyama, J. Phys.: Condens. Matter **3**, 2193 (1991).
- ³⁵L. Pauling, *The Nature of the Chemical Bond*, 3rd edition (Cornell University Press, Ithaca, 1960).
- ³⁶D. G. Pettifor, Bonding and Structure of Molecules and Solids (Oxford University Press, Oxford, 1995).
- ³⁷D. M. Deaven and K. M. Ho, Phys. Rev. Lett. **75**, 288 (1995). See also, J. Maddox, Nature (London) **376**, 209 (1995).
- ³⁸K. M. Ho, A. A. Shvartsburg, B. Pan, Z. Y. Lu, C. Z. Wang, J. G. Wacker, J. L. Fye, and M. F. Jarrold, Nature (London) **392**, 582 (1998).